4th Announcement and Call for Papers



October 3 - 7, 2022 Sendai International Center Sendai, Japan

The 75th Annual Gaseous Electronics Conference & The 11th International Conference on Reactive Plasmas



Organized by GEC Executive Committee International Organizing Committee of ICRP-11

Supported by American Physical Society

Co-sponsored by The Japan Society of Applied Physics

https://www.apsgec.org/gec2022/

General Information

The 75th Annual Gaseous Electronics Conference (GEC-2022) will be held as an international joint conference with the 11th International Conference on Reactive Plasmas (ICRP-11).

GEC, a special meeting of the APS Division of Atomic, Molecular, and Optical Physics (DAMOP), promotes ideas on the physical and chemical processes and dynamics taking place in partially ionized, collisional plasma and between the atoms, molecules, charged particles, photons, waves, and fields. The GEC has a long leadership history of presenting fundamental and basic science contributions on plasma sources, diagnostics, simulation, plasma chemistry, basic phenomena, atomic and molecular processes. In recent years, GEC has also been a leading venue for reporting on emergent areas of plasma-biotechnology, plasma medicine, multiphase plasmas, environmental applications and atmospheric-pressure plasma systems.

ICRP has been taking place based on the initiative of the Division of Plasma Electronics, the Japan Society of Applied Physics since 1991. The subjects covered in ICRP are the entire field of reactive plasmas and their applications to material, environment, energy, space, bio and medical fields with emphasis on basic phenomena, technologies, and the underlying basic physics and chemistry.

The GEC-2022/ICRP-11 will continue its tradition of offering a truly outstanding venue for leading research in low temperature plasma science and collision physics.

Themes ranging from fundamental plasma research to advanced topics will be discussed at GEC-2022/ICRP-11.



Akiu Hot Spring

Scientific Program

The scientific program occurs from Tuesday-Friday with three to four parallel oral sessions consisting of contributed talks, invited talks, and Prize talks, which are 15, 30, and 45 minutes in length, respectively. Contributed posters will be presented during the afternoon poster sessions in the middle of the week.

The main program is preceded by workshops on Monday. Workshop topics are industrial plasmas, catalytic effects in plasma-liquid interaction, functional processes in plasma-solid reactions, and plasmas for space propulsion.

Conference Topics

General Sessions:

1. Atomic & molecular process

1.00 Atomic and molecular collisional and dynamical processes

1.01 Electron and photon collisions with atoms and molecules: excitation

1.02 Electron and photon collisions with atoms and molecules: ionization

1.03 Heavy-particle collisions

1.04 Dissociation, recombination and attachment

1.05 Distribution functions and transport coefficients for electrons and ions

1.06 Other atomic and molecular collision phenomena

2. Plasma science

2.01 Nonequilibrium kinetics of low-temperature plasmas

2.02 Basic plasma physics phenomena in low- temperature plasmas

2.03 Plasma boundaries: sheaths, boundary layers, others

2.04 Plasma-surface interactions

2.05 Plasma diagnostic techniques

2.06 Modeling and simulation: computational methods

2.07 Modeling and simulation: validation and verification

2.08 Modeling and simulation: plasma sources

2.09 Modeling and simulation: chemical reactions

2.10 Modeling and simulation: other

2.11 Glows: dc, pulsed, microwave, others

2.12 Capacitively coupled plasmas

2.13 Inductively coupled plasmas

2.14 Magnetically-enhanced plasmas: ECR, helicon, magnetron, others

2.15 Atmospheric and high pressure plasmas: jets and gliding arcs

2.16 Atmospheric and high pressure plasmas: dielectric barrier and corona discharges

2.17 Atmospheric and high pressure plasmas: catalysis and chemical conversion

- 2.18 Thermal plasmas: arcs, jets, switches, others
- 2.19 Plasmas in liquids
- 2.20 Plasma on or contacting liquids
- 2.21 Plasmas and aerosols
- 2.22 Negative-ion and dust-particle-containing plasmas
- 2.23 Gas phase plasma chemistry
- 2.24 Other plasma science topics

3. Plasma applications

3.01 Plasmas for light production: laser media, glows, arcs, flat panels, and novel sources

- 3.02 Plasma etching
- 3.03 Plasma deposition
- 3.04 Plasma ion implantation
- 3.05 Green plasma technologies: environmental and energy applications
- 3.06 Plasma processing for photovoltaic applications
- 3.07 Biological, medical, and agricultural applications of plasmas
- 3.08 Plasma propulsion and aerodynamics
- 3.09 Plasmas for nanotechnologies, flexible electronics, and other emerging applications
- 3.10 Plasma for other materials processing and synthesis

Workshop:

- 1. Industrial plasma technologies
- 2. Plasma physics for space propulsion technologies
- 3. Functional surfaces in plasma elementary and process-applicable reactions
- 4. Catalytic effects in plasma-liquid interaction



Matsushima

Plenary and Invited Speakers

Plenary:

Will Allis Prize Talk



Makabe, Toshiaki (Keio University, Japan) "40 years with studies on radiofrequency plasma and related transport theory"

The GEC Executive Committee is pleased to recognize Professor Emeritus Makabe as the recipient of the 2022 Will Allis Prize for the Study of Ionized Gases.

Reactive Plasma Award Talk



Hori, Masaru (Nagoya University, Japan) "Evolution of Reactive Plasma Processes by Radical Control" (tentative)

The International Organizing Committee of ICRP-11 is pleased to recognize Professor Hori as the recipient of the 2022 Reactive Plasma Award.

General Sessions:

Adamovich, IgorOhio State University, USANs pulse and hybrid discharges for plasma chemistry and plasma catalysis applications

Agarwal, SumitColorado School of Mines, USAStrategies to enhance etch selectivity during fluorocarbon plasma-assisted atomic layer etching of
silicon-based dielectrics

Akatsuka, HiroshiTokyo Institute of Technology, JapanOptical emission spectroscopy measurement for plasma parameter identification -- from kinetic
modeling to data science

Barrachina, Raul Bariloche Atomic Centre, Argentina Transcending the impact parameter approach by means of a full quantum distorted wave description of ion-atom and ion-molecule collisions

Barret, StevenMassachusetts Institute of Technology, USAElectroaerodynamic propulsion by atmospheric-pressure plasma forces

Bourdon, Anne Ecole Polytechnique, France Chemistry of low-pressure iodine plasmas **Camata, Renato** University of Alabama at Birmingham, USA Plasma synthesis and processing of nanostructured quantum materials

Charles, Christine The Australian National University, Australia Radiofrequency plasma thrusters and related studies

Chang, BingdongTechnical University of Denmark, DenmarkAdvanced plasma processes for three-dimensional nanophotonics

Chiang, Wei-HungNational Taiwan University of Science and Technology, TaiwanMicroplasma technology for nanomaterials synthesis and processing

Choe, Wonho Korea Advanced Institute of Science and Technology, Korea Stabilization of gas-liquid boundary with atmospheric pressure plasma jets

Colgan, JamesLos Alamos National Laboratory, USAThe role of atomic physics in collisional-radiative modeling of tin plasmas for lithography

Cvelbar, Uros Jožef Stefan Institute, Slovenia Nanoplasmonic sensors designed by plasmas

Fontes, ChristopherLos Alamos National Laboratory, USALow-Temperature Lanthanide Spectroscopy Applied to Neutron Star Mergers

Gans, TimoDublin City University, IrelandThe role of surface interactions and negative ions in radio-frequency driven plasmas

Gherardi, Matteo University of Bologn, Italy Deposition of silicon-based thin films with atmospheric-pressure plasmas

Gibson, AndrewRuhr University Bochum, GermanyUnderstanding and control of chemical pathways in molecular gas-based plasma sources

Hamdan, AhmadUniversité de Montréal, CanadaProduction of nanomaterials by pulsed electrical discharges in dielectric liquid

Hara, KentaroStanford University, USAInstabilities and turbulent processes in low-temperature magnetized plasmas

Haruyama, Tetsuya Kyushu Institute of Technology, Japan Plasma / liquid (P/L) interfacial reaction for gas reduction reaction

Helmersson, UlfLinköping University, SwedenHigh-power pulsed gas-flow sputter synthesis of nanoparticles, core/shell nanoparticles, and
extended chain-like complexes

Hill, ChristianVienna International Centre, AustriaAtomic and molecular data activities at the IAEA in support of nuclear fusion energy research

Hoshino, Masamitsu Sophia University, Japan Quantitative measurements of electron collision cross sections and their database related to plasma modeling

Iqbal, MuzammilKorea Institute of Machinery and Materials, KoreaPlasma assisted green ammonia production from water and nitrogen at atmospheric pressure

Ishikawa, KenjiNagoya University, JapanPlasma-functional nitrogen effects on biological, medical, and agricultural applications

Kadyrov, AlisherCurtin University, AustraliaIon-induced differential ionisation of helium at intermediate energies

Kamataki, Kunihiro Kyushu University, Japan

Measurements of strength and fluctuation of 2D electric fields in plasmas using a fine particle trapped with laser tweezers

Kersten, Holger Kiel University, Germany

Plasma diagnostics of a micro-discharge intended for in situ TEM studies

Komuro, Atsushi The University of Tokyo, Japan

Modeling of chemical reaction processes induced by an atmospheric-pressure streamer discharge in air

Lacoste, DeannaKing Abdullah University of Science and Technology, Saudi ArabiaNon-equilibrium plasma discharges for combustion applications: experiments and diagnostics

Laroussi, MounirOld Dominion University, USACold atmospheric plasmas in biology and medicine: The fundamentals

Levko, Dmitry Esgee Technologies Inc., USA Development of validated fluorocarbon plasma chemistry for multi-dimensional modeling of semiconductor plasma etch processes

Likhanskii, Alexandre Applied Materials, Inc., USA Bridging the gap between fluid and kinetic plasma simulations for industrial plasma sources

Lietz, AmandaNorth Carolina State University, USAInsights from modeling low-pressure high-voltage dual-frequency capacitively coupled plasmas

Lim, YegeonKorea Advanced Institute of Science and Technology, KoreaBenchmark experiments of the power law parametrization of the effective ion collecting area of a
planar Langmuir probe in low temperature plasmas

Liu, Dingxin	Xi'an Jiaotong University, China
Air discharge plasma used	for preventing SARS-CoV-2 infections

Maguire, Paul Ulster University, UK

Generating enhanced chemical reactions inside highly charged microscale droplets for remote delivery of reactive radicals and high purity nanomaterials

Mesbah, Ali University of California, Berkeley, USA The promise of data-driven methods for characterization, diagnostics and control of plasma processing of complex surfaces

Nagashima, Yasuyuki Tokyo University of Science, Japan Progress in research using positronium negative ions

Namba, ShinichiHiroshima University, JapanGeneration of stationary high-density cascade arc plasmas and its application to plasma windows

Nunomura, ShotaNational Institute of Advanced Industrial Science and Technology,
JapanPlasma induced electronic defects: formation and recovery mechanism for advanced processing

O'Connor, Robert Dublin City University, Ireland

Optimisation and understanding of plasma enhanced atomic layer deposition processes using quasi in-situ X-ray photoelectron spectroscopy

Oehrlein, Gottlieb University of Maryland, USA

Gas phase and surface infrared studies of plasma-catalysis

Ptasinska, SylwiaUniversity of Notre Dame, USADissociative electron attachment to amides

Puac, NevenaInstitute of Physics Belgrade, SerbiaRole of atmospheric pressure plasma in triggering of cell mechanisms in plant calli

Ren, Xueguang Xi'an Jiaotong University, China Electron collision with molecules and clusters

Scheiner, Brett Los Alamos National Laboratory, USA Electron Sheaths and Fireballs

Schücke, LarsRuhr-University Bochum, GermanyReactive oxygen and nitrogen species in a twin surface dielectric barrier discharge for conversion
of volatile organic compounds

Shigeta, MasayaTohoku University, JapanComputational studies of thermal-plasma-induced turbulence on nanopowder generation and
sustained arc discharge

Shinoda, Kazunori Hitachi Ltd., Japan

Plasma-assisted, thermal-cyclic atomic-layer etching for selective removal of thin films

Smolyakov, Andrei University of Saskatchewan, Canada Plasma flow and acceleration in the magnetic nozzle

Sun, Jing-YuDalian University of Technology, ChinaResonant sheath heating in weakly magnetized capacitively coupled plasmas due to electron-
cyclotron motion

Suzuki, Haruka Nagoya University, Japan High-speed synthesis of silver nanoparticles by combination of AgNO₃ liquid flow and a microwave plasma

Tachikawa, MasanoriYokohama City University, JapanPositron binding in molecules

Takashima, KeisukeTohoku University, JapanNitrogen vibrational excitation in a non-self-sustained discharge plasma toward efficient nitrogenfixation processes

Trelles, Juan P.University of Massachusetts Lowell, USASolar-plasma reactors and processes for sustainable chemical synthesis

Trieschmann, JanKiel University, GermanyMachine learning plasma-surface interactions: from low to high fidelity surrogate models

Uchida, GiichiroMeijo University, JapanNext-generation Li-ion battery achieved by the low temperature plasma processes

Veilleux, JocelynUniversite de Sherbrooke, CanadaThermal plasma synthesis of nanoparticles for application in lithium batteries

Zhang, ChengChinese Academy of Sciences, ChinaIonization wave propagation in nanosecond pulsed discharge and its application

Zhang, YuantaoShandong University, ChinaModeling study on interactions of code atmospheric plasmas and vegetable oil

Zheng, BocongFraunhofer USA Center Midwest, Michigan State University, USAElectron power absorption in magnetron sputtering discharges

Workshops:

Industrial plasma technologies

Moriya, Tsuyoshi Tokyo Electron Limited, Japan New challenges on semiconductor plasma manufacturing

Kim, JaehoSamsung Electronics, KoreaApplications of plasma-enhanced deposition technologies in the semiconductor industry

Lee, Dae Hoon Korea Institute of Machinery and Materials, Korea Plasma for a clean and carbon-neutral world

Kenney, JasonApplied Materials, USAModeling and simulation of plasmas for etch applications

Ohtake, HirotoHitachi High Technologies, JapanThermal cyclic atomic-level etching in 3D ULSI device fabrication

Tatsumi, TetsuyaSony Semiconductor Solutions Corporation, JapanQuantitative control of plasma and surface reactions for dielectric film etching

Plasma physics for space propulsion technologies

Boswell, Rod Boswell Technologies, Australia From laboratory to orbit: Mothballs in Space

Merino, MarioUniversidad Carlos III de Madrid, SpainElectrodeless plasma thrusters and magnetized plasma expansions for space propulsion

Little, JustinUniversity of Washington, USAMagnetically expanding plasmas for space propulsion

Fruchtman, AmnonHolon Institute of Technology, IsraelThe effects of collisions and oscillating fields on the thrust in electric propulsion

Mazouffre, Stéphane CNRS - ICARE laboratory, France Electron thermodynamics and ion transport in the magnetic nozzle of electrodeless electric thrusters

Kawashima, ReiShibaura Institute of Technology, JapanAnatomy of cross-field electron transport by steady and unsteady plasma structures in Hall
thrusters

Cho, ShinatoraJapan Aerospace Exploration Agency, JapanIn-space electric propulsion system enabling JAXA commercial removal of debris demonstration(CRD2): Challenges and relevant physics

Functional surfaces in plasma elementary and process-applicable reactions

Kurahashi, Mitsunori National Institute for Material Science, Japan Application of hyperthermal spin- and alignment-controlled O₂ beam to surface reaction analysis

Nakamura, Hiroaki National Institute for Fusion Science, Japan Integrated simulation for excited hydrogen molecule formed by recombination on carbon surfaces

Ibano, Kenzo Osaka University, Japan

Fibrous nanostructures formation using helium plasma and their applications as functional materials

Nozaki, Tomohiro Tokyo Institute of Technology, Japan Gas reforming by plasma-catalyst coupling

Kim, June YoungSeoul National University, KoreaKinetic simulation of narrow gap discharge

Stamate, EugenTechnical University of Denmark, DenmarkAdvanced functional thin films for energy conversion and storage devices deposited by plasma-
based processes

Catalytic effects in plasma-liquid interaction

Zhou, RenwuXi'an Jiaotong University, ChinaCold atmospheric plasma bubbles: Reactive environments for sustainable processing and
activation

Murakami, Tomoyuki Seikei University, Japan Graph-based approach to catalytic effects in plasma-exposed liquids

Shimizu, NaohiroNagoya University, JapanWater dessociation by high-power pulse plasma

Bogaerts, Annemie University of Antwerp, Belgium Modeling of plasma-liquid interaction

Contributed Papers

Call for Contributed Papers

Abstracts:

Contributed papers will be given orally in a 15-minute timeslot (12 minutes for presentation and 3 minutes for questions) or as a poster. For either mode, authors must submit an abstract, which succinctly identifies the problem, describes the approach, and summarizes the status or result of the completed or intended intellectual contribution. Contributors must submit abstracts using the Abstract Submission site (https://www.apsgec.org/gec2022/abstracts.php).

Before you start:

- Know the number and the order of authors
- Proofread the abstract
- Abstracts are limited to 1,300 characters (about 250 words)
- Note the sorting category (category list) or focus topic
- Presentation Summary: Please provide a brief summary of your presentation written for a general audience. The summary should describe the "takehome" messages of your talk and their implications.

To submit an abstract, you must:

- 1. Use the GEC sorting category list when submitting
- 2. Know the correct ordering of authors and collaborators, and
- 3. Submit abstract content. The website will ask you for an APS membership number. If you are not an APS member, you should type "GEC abstract" in the member ID box when submitting.

For general information about APS abstract submission, please visit the following site (https://www.aps.org/meetings/abstract/submit.cfm).

Abstract Submission opens:

March 9, 2022

Abstract Submission deadline:

June 10, 2022 (4:00 pm US Central Time)



Tohoku University

Awards and Grants

Awards and Grants Deadlines

The GEC Student Award for Excellence:

The GEC Student Award for Excellence recognizes the important contributions students make to the GEC every year with their research, presence, and passion. One awardee will be selected and receive a \$1,000 USD prize. The eligibility and nomination materials can be found on the **Awards site** (https://www.apsgec.org/gec2022/awards.php).

The application materials must be emailed as a single PDF file to the chair of the GEC 2022 Student Award for Excellence Committee, **Dr. Stephan Reuter** (stephan.reuter@polymtl.ca) **by 4:00 pm US Central Time on June 10, 2022**.

The GEC Student Poster Prize:

The GEC Student Poster Prize recognizes three student presented research posters for their contribution to the work and future of GEC. The eligibility and nomination materials can be found on the **Awards site** (<u>https://www.apsgec.org/gec2022/awards.php</u>).

Student applications are to be emailed to the chair of the GEC 2022 Student Poster Prize Committee, **Dr. Masaya Shigeta** (shigeta@tohoku.ac.jp) **by noon US Central Time on September 26, 2022**.

The Student Travel Grant:

The Student Travel Grant provides funding to offset the cost of attending the conference in person (onsite). The grant will cover the full registration cost of the conference and partial coverage for lodging and travel. Nomination materials can be found on the **Grants and Scholarship site** (https://www.apsgec.org/gec2022/grants_scholarships.php).

Submit nominations to GEC Scholarship chair, **Dr. Tetsuji Shimizu** (tetsuji.shimizu@aist.go.jp) **by 4:00 pm US Central Time on June 10, 2022**.

The Child Care Grant:

The Child Care Grant provides up to \$400 to attendees who bring young children to the meeting or who incur extra expense in leaving dependents at home (i.e., daycare, babysitting, or caregiver services), or who need to fund additional activities or services to address accessibility issues. The Application materials can be found on the **Grants and Scholarship site**

(https://www.apsgec.org/gec2022/grants_scholarships.php).

Submit applications to GEC Scholarship chair, **Dr. Tetsuji Shimizu** (tetsuji.shimizu@aist.go.jp) **by noon US Central Time on September 1, 2022.**

Non-Technical Events

Special Events

Student Networking Event:

Thursday, October 6, 2022.

The event consists of a few roundtable discussions with students and researchers. Free lunch is provided. Good opportunity to learn about the inside story of research, work environment at companies and universities, career plan, tips of experiments, and more.

Women in Physics:

Tuesday, October 4, 2022.

Lectures by female researchers who are active on the cutting edge of science will be held. The scientists will talk not only about the research they are working on, but also about their own experiences, including their career paths.

Social Events

Welcome Reception: Monday, October 3, 2022.

GEC Reception and Banquet:

Thursday, October 6, 2022.

Closing Ceremony:

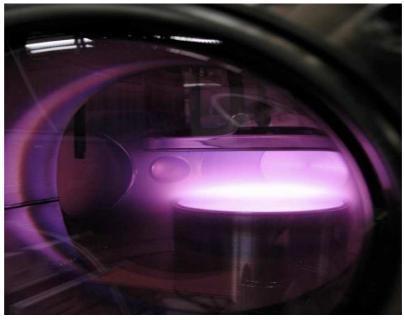
Friday, October 7, 2022.

Committees

GEC Executive Committee Members

Chair: Julian Schulze, University of Bochum, Germany Chair elect: Shahid Rauf, Applied Materials Inc. Past secretary: Gabe Xu, University of Alabama in Huntsville Secretary: Toshiro Kaneko, Tohoku University, Japan Secretary elect: Scott Baalrud, University of Michigan Treasurer: Aranka Derzsi, Wigner Research Centre for Physics, Hungary Kallol Bera, Applied Materials Inc. Mark Koepke, West Virginia University Mark Kushner, University of Michigan Sandra Quintanilla, University of North Texas Stephan Reuter, Ecole Polytechnique de Montreal, Canada Tetsuji Shimizu, National Institute of Advanced Industrial Science and Technology, Japan

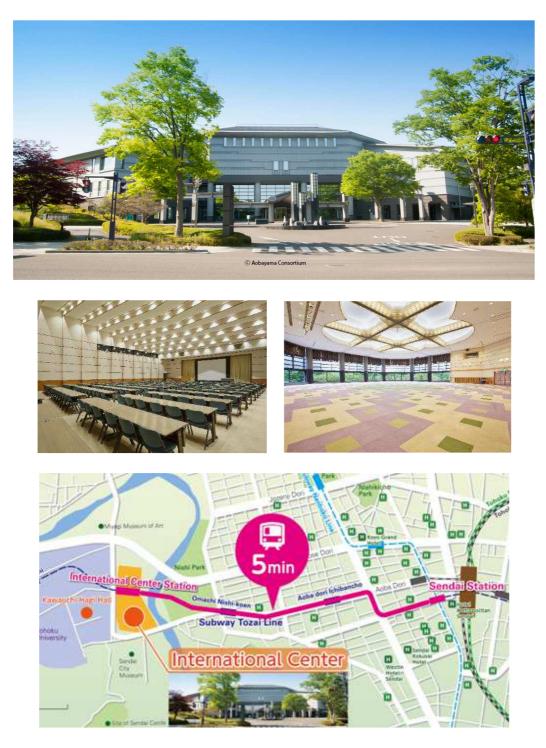




GEC reference reactor

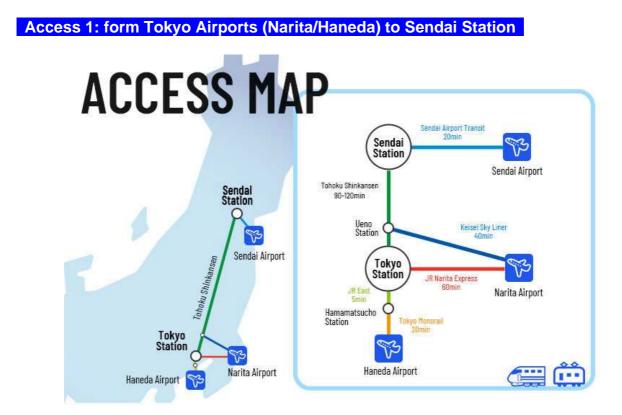
Conference Venue

GEC-2022/ICRP-11 is planned to be held as an in-person meeting at **the Sendai International Center (http://www.aobayama.jp/english/)** located in Sendai, Japan. If the Covid19 pandemic does not allow to hold an onsite conference, a fully virtual meeting will be organized.

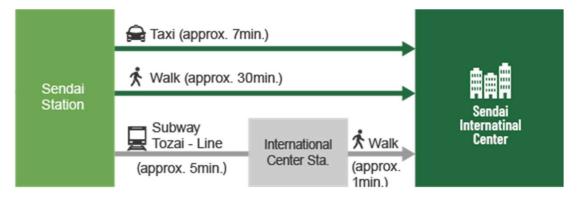


Travel Information

Tokyo has two international airports, Haneda and Narita, with many international flights, making it easy to get to Japan from anywhere in the world. There are two daily direct flights from Narita airport to Sendai. It takes 30 minutes by train from Sendai Airport to downtown Sendai. On the other hand, if you are traveling by train from Narita or Haneda airports, you can take the Shinkansen (bullet train) from the respective airports to Sendai via Tokyo Station. It takes 90 minutes from Tokyo Station to Sendai Station by Shinkansen.



Access 2: form Sendai Station to the venue



Hotel Accommodation

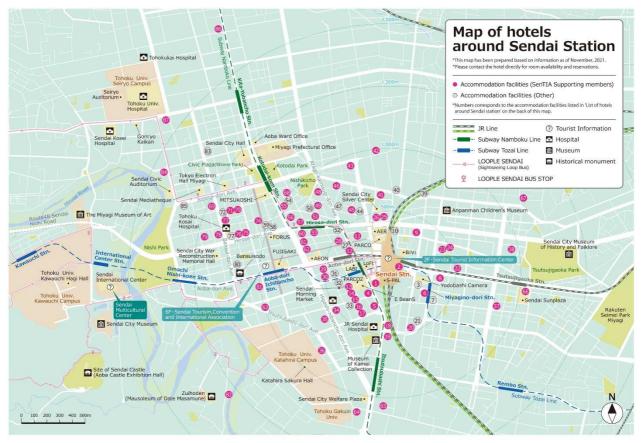
There are many hotels in Sendai. We recommend that you make your own reservations at the hotel reservation websites listed below.

Expedia

Booking.com

Trivago

Map of Hotels:



[Accommodation facilities (SenTIA Supporting members)

• Within 1,000 meters radius from Sendai Stn.

•	 Within 500 meters radius from Sendai Stn. 			
No	Name	TEL	Rooms	
1	HOTEL METROPOLITAN SENDAI	81-22-268-2525	295	
2	HOTEL METROPOLITAN SENDAI EAST	81-22-302-3373	282	
4	Hotel Monterey Sendai	81-22-265-7110	206	
5	WASHINGTON HOTEL SENDAI	81-22-745-2222	223	
6	HOTEL VISTA SENDAI	81-22-385-6222	238	
8	SENDAI GARDEN PALACE	81-22-299-6211	66	
9	Comfort Hotel Sendai East	81-22-792-8711	202	
1	HOTEL Green Pacific	81-22-221-8888	92	
12	Richmond Hotel Premier Sendai Ekimae	81-22-716-2855	183	
13	HOTEL Green Well	81-22-216-6155	47	
14	HOTEL UNISITE SENDAI	81-22-716-0123	144	
15	HOTEL CENTRAL SENDAL	81-22-711-4111	97	
16	SENDAI BUSINESS HOTEL STATION FRONT	81-22-262-3211	250	
17	HOTEL Green Mark	81-22-224-1050	140	
18	Toyoko Inn Sendai-eki Nishi-guchi Chuo	81-22-726-1045	286	
19	APA Villa Hotel Sendai-Eki Itsutsubashi	0570-023-111	610	
20	ANA Holiday Inn SENDAI	81-22-256-5111	165	
22	Hotel Grand Bach Sendai	81-22-296-0660	151	
23	Toyoko Inn Sendai Higashi-guchi No.1	81-22-256-1045	208	
24	Toyoko Inn Sendai Higashi-guchi No.2	81-22-298-1045	120	
25	HOTEL JAL CITY SENDAL	81-22-711-2580	238	
26	Hotel Monte Hermana SENDAI	81-22-721-7501	275	
28	HOTEL Premium Green PLUS	81-22-212-1255	117	
29	HOTEL KEIHAN SENDAI	81-22-263-0321	201	
30	ALMONT HOTEL SENDAL	81-22-212-6551	141	
34	Sendai Kokusai Hotel	81-22-268-1111	234	

No		TEL	Rooms
35	The Westin Sendai	81-22-722-1234	292
36	Aisaki Ryokan (Inn)	81-22-264-0700	15
37	HOTEL MIELPARQUE SENDAI	81-22-792-8111	122
38	Oka no Hotel	81-22-256-7311	35
41	Richmond Hotel Sendai	81-22-722-0055	344
42	HOTEL SHIRAHAGI	81-22-265-3411	28
43	SENDAI ROYAL MAYFLOWER	81-22-262-5411	182
45	Toyoko Inn Sendai Nishi-guchi Hirose-dori	81-22-721-1045	210
46	Daiichi Inn Park	81-22-213-0089	85
48	HOTEL HOKKE CLUB SENDAI *Scheduled to close on January 5, 2022	81-22-224-3121	151
49	HOTEL Green Selec	81-22-217-3117	77
51	R&B Hotel Sendai Hirose-dori Ekimae	81-22-726-1919	202
53	dormy inn EXPRESS Sendai Hirose-dori	81-22-715-7077	120
55	LIBRARY HOTEL HIGASHI-NIBANCHO	81-22-221-7666	230
56	Mitsui Garden Hotel Sendai	81-22-214-1131	224
57	KOYO GRAND HOTEL	81-22-267-5111	149
60	Super Hotel Sendai / Hirosedori	81-22-224-9000	173
61	HOTEL Premium Green Hills	81-22-722-1501	118
62	HOTEL CROWN HILLS SENDAI AOBADORI	81-22-262-1355	154
63	Hotel Bel Air Sendai	81-22-217-8511	125

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TEL Green Park		
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	01-22-203-0171	72
TEL Premium Green SOVEREIGN	81-22-227-2322	92
sule Hotel Leaves	81-22-261-8020	120
NA & CAPSULE CURE KOKUBUNCHO	81-22-713-8526	186
le Hotel Sendai Kokubuncho	81-22-261-7711	202
el Grand Terrace Sendai Kokubun-cho	81-22-262-7755	294
'EL Green With	81-22-261-3737	78
RI NO HOTEL SENDAI	81-22-713-5888	77
FEL Green Arbor	81-22-213-8990	64
FEL PEARL CITY SENDAL	81-22-262-8711	166
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Na	Name		
86	HOTEL Green City	81-22-219-2691	80
87	BANSUITEI IKOISO	81-22-222-7885	14

Information about Entering Japan

Based on the New Border Measures, from June 1, 2022, requirements regarding on-arrival testing, potential self-quarantine periods and the place of accommodation after entry into Japan are expected to depend on the country/region of stay before arrival in Japan ("Red", "Yellow" and "Blue" categories: https://www.mhlw.go.jp/stf/covid-19/border_category.html).

Most GEC attendees are expected to belong to the blue group. For this group, regardless of the vaccination status of the entrants/returnees, on-arrival testing, home quarantine and other measures are not required. For FAQ about Quarantine measures, please see:

https://www.mhlw.go.jp/stf/covid-19/bordercontrol.html

Information about VISA

Firstly, please complete the advanced registration.

For all non-Japanese on-site participants in GEC 2022 / ICRP-11, a VISA is required to enter Japan at present. A "certificate for completion of Registration to the Entrants, Returnees Follow-up System (ERFS)" is required to obtain a VISA to Japan.

An application for a visa is made by the applicant him/herself at the Japanese overseas establishments with jurisdiction over the area in which the applicant resides or those with jurisdiction over the country/region of which the applicant's passport is issued.

Before you apply for a VISA, please ask to the Japanese Embassy or Consulate General near your place in the country by which your passport is issued to check the necessary documents and procedures for your VISA application.

VISA | Ministry of Foreign Affairs of Japan:

https://www.mofa.go.jp/j_info/visit/visa/index.html

Please note that an invitation letter in English will be provided by the GEC2022 office. Please inform the Congress Secretariat if you need documents other than the invitation letter in English for your VISA application.

For inquiries

ICRP-11 Congress Secretariat E-mail : icrp11@senkyo.co.jp

Calendar of Events

Abstract Submission deadlineJune 10, 2022Student Travel Grant deadlineJune 10, 2022GEC Student Award for Excellence deadlineJune 10, 2022Author Notices of AcceptanceAugust 2, 2022Early Registration deadlineAugust 31, 202GEC Student-Poster Prizes deadlineSeptember 26

June 10, 2022 (4:00 pm US Central Time) June 10, 2022 June 10, 2022 August 2, 2022 August 31, 2022 September 26, 2022

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